

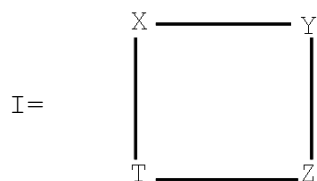
Abstract

Process that enables the creation of nanometric structures
by self-assembly of block copolymers

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The invention relates to a process that enables the
creation of nanometric structures by self-assembly of block
copolymers, at least one of the blocks of which results
10 from the polymerization of monomers comprising at least one
cyclic entity corresponding to the formula I.

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where X= Si (R₁, R₂) ; Ge (R₁, R₂)

20 Z= Si (R₃, R₄) ; Ge (R₃, R₄) ; O ; S ; C (R₃, R₄)

Y= O ; S ; C (R₅, R₆)

T= O ; S ; C (R₇, R₈)

R₁, R₂, R₃, R₄, R₅, R₆, R₇, R₈ are selected from hydrogen,
25 linear, branched or cyclic alkyl groups, with or without
heteroatoms, and aromatic groups with or without
heteroatoms.